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Author

Anders, A.

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Invited Talk

To be presented at the
7th EUROPEAN VACUUM CONFERENCE, **EVC-7**,
being organized jointly with the
3rd EUROPEAN TOPICAL CONFERENCE ON HARD COATINGS, **ETCHC-3**.

A reviewed version of the full paper may be published in VACUUM.

Energetic Deposition using Filtered Cathodic Arc Plasmas

André Anders

Lawrence Berkeley National Laboratory, University of California,
Berkeley, California 94720, USA

Abstract April 2001

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ENERGETIC DEPOSITION USING FILTERED CATHODIC ARC PLASMAS

A. Anders, Lawrence Berkeley National Laboratory, University of California, 1 Cyclotron Road, Mailstop 53, Berkeley, California 94720, USA.

Energetic deposition can be defined as a film deposition process in which a significant fraction of particles arrives at the substrate surface with a kinetic energy greater than the bulk displacement energy of the substrate. Examples of energetic deposition processes are ion beam assisted deposition (IBAD), plasma immersion ion deposition, pulsed laser deposition, and cathodic arc deposition. This work focuses on the production, properties, and use of filtered cathodic arc plasmas. Even without bias, dense metal and metal compound films can be obtained. Biasing the substrate, e.g. using the pulsed biasing technique of plasma immersion ion deposition, extends the possibilities of tuning film properties such as adhesion, stress, surface roughness, elastic modulus, hardness, and density. The formation of ultrathin ta-C (diamondlike carbon) films and metal films will be discussed.